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4.55 ENGLISH 550. ncstudio v5.5.60 english setup.rar. Jun 20, 2021 When the above said packages appear on my PC, I press on "Open with Archive Manager", but it does not work, I can not open them. A: You can download the trial version of WinRAR from here, extract it to a temporary folder, then run the Ncstudio installer in the temporary folder. The present invention relates to a drying apparatus for drying a substrate comprising, for example, a semiconductor wafer or the like, and more particularly, to a drying apparatus for drying a substrate, which is excellent in cleaning performance and which is suitable for drying a substrate with low stress applied thereto. In a drying step of the semiconductor manufacturing process, a substrate such as a semiconductor wafer is held by a spin chuck and then subjected to spin-drying by rotary drier. In recent years, a spin-dryer has been used to meet demands of high-throughput production, and therefore, the spin-dryer has become very large in scale. The spin-dryer, which is large in scale, is provided with a turntable, in which a number of substrate carriers are provided, on which a plurality of semiconductor wafers are set; a lid for covering the turntable; a plurality of nozzle members each provided at its center with a nozzle hole for forming a thin film of, for example, deionized water on a surface of the semiconductor wafer; and a power for driving the turntable to rotate. Further, an annular space is formed between the turntable and the lid. In the spin-dryer of such a construction, a number of semiconductor wafers are held by the substrate carriers and are subjected to spin-drying by rotating the turntable. A substrate to be dried in the spin-dryer mentioned above is generally maintained at a temperature of about 20°C by a chiller and is then introduced into the spin-dryer. A sheet of, for example, a polyethylene terephthalate film is provided in the bottom portion of the spin-dryer for preventing water droplets attached to the semiconductor wafers from dropping. When the semiconductor wafer is subjected to spin-drying in the spin-dryer, the inner wall

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